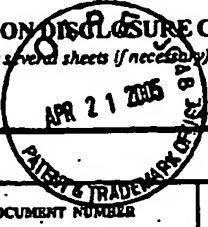


INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) FIS920040011US1		Application Number 10/783,938	
				Applicant(s) Rosenbluth, et al.			
				Group Art Unit 2892 2851			



U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

U.S. PATENT APPLICATION PUBLICATIONS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS		(Including Author, Title, Date, Pertinent Pages, Etc.)
D.R.		1) "Method Of Measuring The Spatial Resolution Of A Photoresist" - J.A. Hoffnagle, et al. 2002 Optical Society of America - p. 1776. 2) "Reduction Of ASIC Gate-Level Line-End Shortening By Mask Compensation" - J. Garofalo, et al. SPIE Vol. 2440 - Optical/Laser Microlithography VIII - p. 171
D.R.		3) "Improved Modeling Performance With An Adapted Vectorial Formulation Of The Hopkins Imaging Equation" - Adam, et al. - p. 78-91 4) "Simulation Of Imaging And Stray Light Effects In Immersion Lithography" - Hafeman, et al. SPIE Vol. 5040 - Optical Microlithography XVI, ed. Anthony Yen (2003), p. 700

EXAMINER <i>Ritf</i>	DATE CONSIDERED 9/28/05
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.